

Xu Yang

List of Publications by Year in descending order

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papers

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citations

1040056

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1474206

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#	ARTICLE	IF	CITATIONS
1	Highly efficient planarization of sliced 4H-SiC (0001) wafer by slurryless electrochemical mechanical polishing. <i>International Journal of Machine Tools and Manufacture</i> , 2019, 144, 103431.	13.4	48
2	Investigation of anodic oxidation mechanism of 4H-SiC (0001) for electrochemical mechanical polishing. <i>Electrochimica Acta</i> , 2018, 271, 666-676.	5.2	39
3	Obtaining Atomically Smooth 4H-SiC (0001) Surface by Controlling Balance Between Anodizing and Polishing in Electrochemical Mechanical Polishing. <i>Nanomanufacturing and Metrology</i> , 2019, 2, 140-147.	3.0	27
4	Ultrasonic-assisted anodic oxidation of 4H-SiC (0001) surface. <i>Electrochemistry Communications</i> , 2019, 100, 1-5.	4.7	26
5	Efficient and slurryless ultrasonic vibration assisted electrochemical mechanical polishing for 4H-SiC wafers. <i>Ceramics International</i> , 2022, 48, 7570-7583.	4.8	21
6	Dominant factors and their action mechanisms on material removal rate in electrochemical mechanical polishing of 4H-SiC (0001) surface. <i>Applied Surface Science</i> , 2021, 562, 150130.	6.1	17
7	Surface Modification and Microstructuring of 4H-SiC(0001) by Anodic Oxidation with Sodium Chloride Aqueous Solution. <i>ACS Applied Materials & Interfaces</i> , 2019, 11, 2535-2542.	8.0	16
8	Etching Characteristics of Quartz Crystal Wafers Using Argon-Based Atmospheric Pressure CF ₄ Plasma Stabilized by Ethanol Addition. <i>Nanomanufacturing and Metrology</i> , 2019, 2, 168-176.	3.0	13
9	Optimization of Gas Composition Used in Plasma Chemical Vaporization Machining for Figuring of Reaction-Sintered Silicon Carbide with Low Surface Roughness. <i>Scientific Reports</i> , 2018, 8, 2376.	3.3	11